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Contents

vii *Symposium Committee*
xi *Conference Committee*

OPTICAL METROLOGY METHODS I

- 12769 03 **Guided filtering based surface recovery algorithm for white light interferometry** [12769-2]
- 12769 04 **Long binary coding design for absolute positioning using genetic algorithm** [12769-4]
- 12769 05 **High-speed spectral confocal signal collection method based on acquisition and tracking algorithm with variable window-width** [12769-5]
- 12769 06 **Spectral interferometry for thin film information by fitting Fourier transform spectrum** [12769-6]

OPTICAL METROLOGY METHODS II

- 12769 09 **Optical method for depth measurement of high aspect ratio 3D microstructure** [12769-9]

OPTICAL METROLOGY METHODS III

- 12769 0B **Comprehensive advancements in automatic digital manufacturing of spherical and aspherical optics (Invited Paper)** [12769-11]
- 12769 0C **Improved dispersion-coded full-range spectral interferometry for large-depth samples** [12769-12]
- 12769 0D **Fast calibration based photometric stereo for multiscale metallic surface measurement** [12769-13]
- 12769 0E **High-quality super-resolution lensless imaging with Fresnel zone aperture** [12769-14]

OPTICAL METROLOGY METHODS IV

- 12769 0F **Full-field modeling and calibration of 3D interference fringe volume with line-shaped Gaussian beam intersection (Invited Paper)** [12769-15]
- 12769 0H **Measurement and analysis of a 4"-18" aperture dual-beam Fizeau interferometer** [12769-17]

OPTICAL METROLOGY METHODS V

- 12769 OJ **Automated sampling path planning model for complex surface of cylinder gear based on laser scanning techniques** [12769-20]
- 12769 OK **Error compensation for form errors of plate beamsplitter in near optical coaxial phase measuring deflectometry with reflection error model** [12769-21]
- 12769 OL **Mid-spatial frequency error measurement of large aperture lenses** [12769-22]
- 12769 OM **A deep-learning approach for rapid prediction of spectral responses of meta-atoms** [12769-23]
- 12769 ON **Analysis of vibration causes of large aperture wafer under vertical support** [12769-24]

OPTICAL METROLOGY APPLICATIONS I

- 12769 OP **Spectral analysis algorithm of vibration effect in phase-shifting interferometry (Invited Paper)** [12769-26]
- 12769 OQ **Dynamic angle measurements involving different optical null-indicator types (Invited Paper)** [12769-27]

OPTICAL METROLOGY APPLICATIONS II

- 12769 OT **Single-shot dispersive interferometry for inline surface inspection** [12769-31]
- 12769 OU **Dynamic combined measurement of multiple laser trackers and application** [12769-32]
- 12769 OV **Optimization of adaptive digital fringe method in PMD** [12769-33]
- 12769 OW **Geometric characteristics measurement technique for film cooling holes based on spectral interferometry system** [12769-34]

OPTICAL METROLOGY APPLICATIONS III

- 12769 OY **Evaluation of atmospheric temperature uncertainty caused by platform attitude fluctuation** [12769-36]

- 12769 10 **Codes coupling optimization for absolute measurement** [12769-38]
- 12769 11 **Frequency modulation continuous wave speed-distance synchronous measurement with variable period frequency parameter estimation traced to optical frequency comb** [12769-40]

POSTER SESSION

- 12769 12 **A quantitative reconstruction method for background-oriented Schlieren by reducing the weight matrix** [12769-41]
- 12769 13 **Angular determination algorithm for three-dimensional autocollimation measurements** [12769-42]
- 12769 16 **Analysis of defocus error on the absolute measurement of spherical surface** [12769-45]
- 12769 17 **Efficient GPU acceleration for phase unwrapping algorithm** [12769-46]
- 12769 18 **Bat-wing elimination algorithm based on the CNN in white-light interferometry** [12769-47]
- 12769 1A **Multi-wavelength laser interferometer control system design** [12769-49]
- 12769 1D **Analysis of autocollimator measurement system based on quaternion algorithm for 6-DOF** [12769-52]
- 12769 1F **Swing-arm profilometer design for high steepness optical aspheric surfaces** [12769-54]
- 12769 1G **An extended light source based on multimode fiber in interferometers** [12769-55]
- 12769 1H **A smartphone-based device for automatically calibrating wave-front systematical error** [12769-56]
- 12769 1J **An iterative reconstruction method for photoacoustic tomography in heterogeneous media based on point source response** [12769-58]
- 12769 1K **Novel parallel measurement method of spectral confocal sensor with multi-point scanning** [12769-64]

DIGITAL POSTER SESSION

- 12769 1N **Algorithm for detection and classification of small objects on a complicated background to automated robotic complex** [12769-19]
- 12769 1O **Preprocessing and classification of objects based on neural network models built using memristors' elements** [12769-39]

- 12769 1P **New indicators and standards for measuring of the end mill's helical groove by image processing** [12769-59]
- 12769 1Q **Deep learning-based depth map defect removal for industrial applications** [12769-60]
- 12769 1R **Attention map-guided multi-scale haze removal method for industrial inspection system** [12769-61]
- 12769 1S **Planning the trajectory of an object in a confined space using stationary machine vision systems** [12769-62]
- 12769 1T **Combining tensometric and video data in solving problems of eliminating dynamic effects during the movement of a manipulator with flexible links** [12769-63]

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